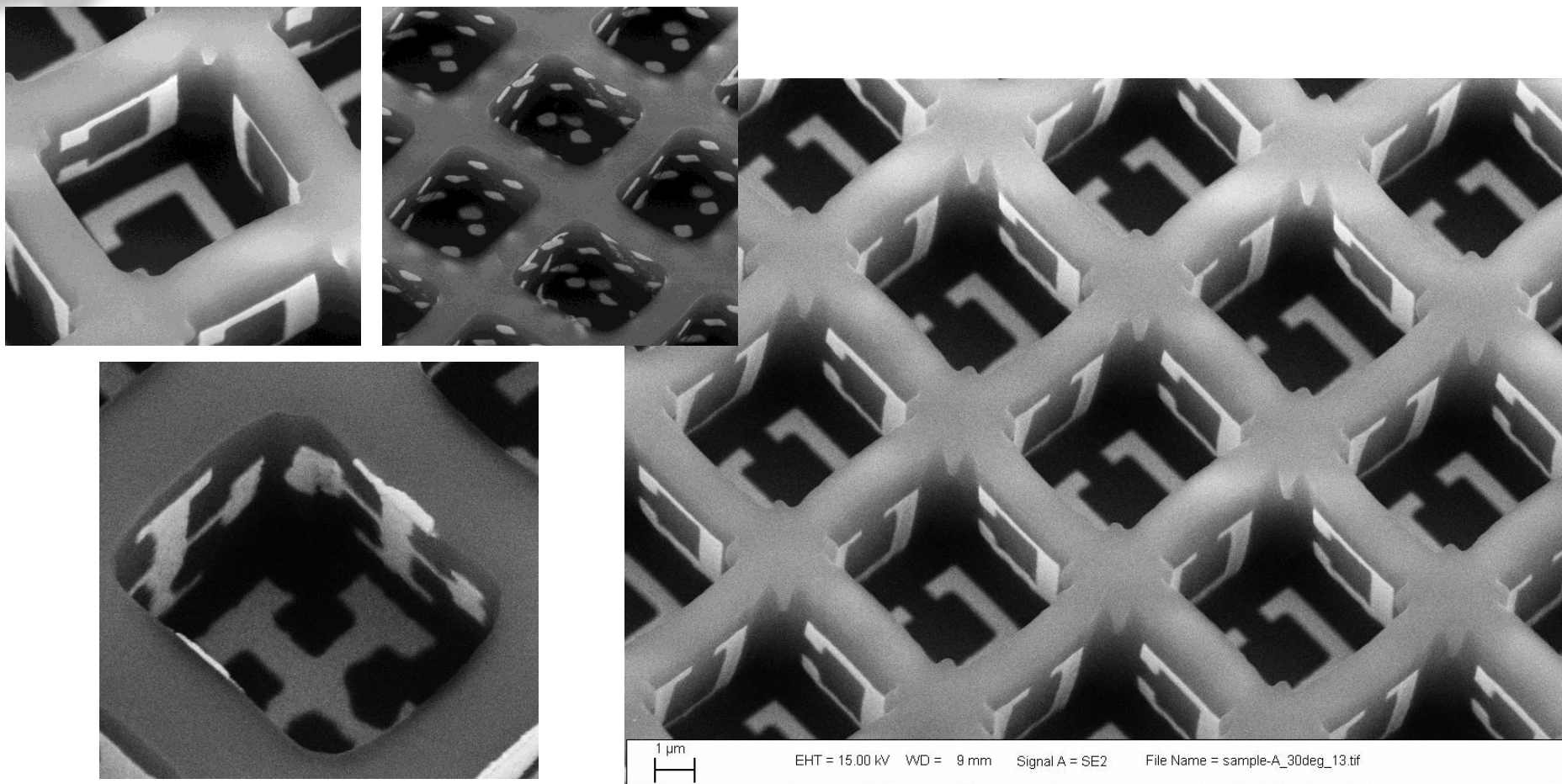


Membrane Projection Lithography

SAND2013-7376P

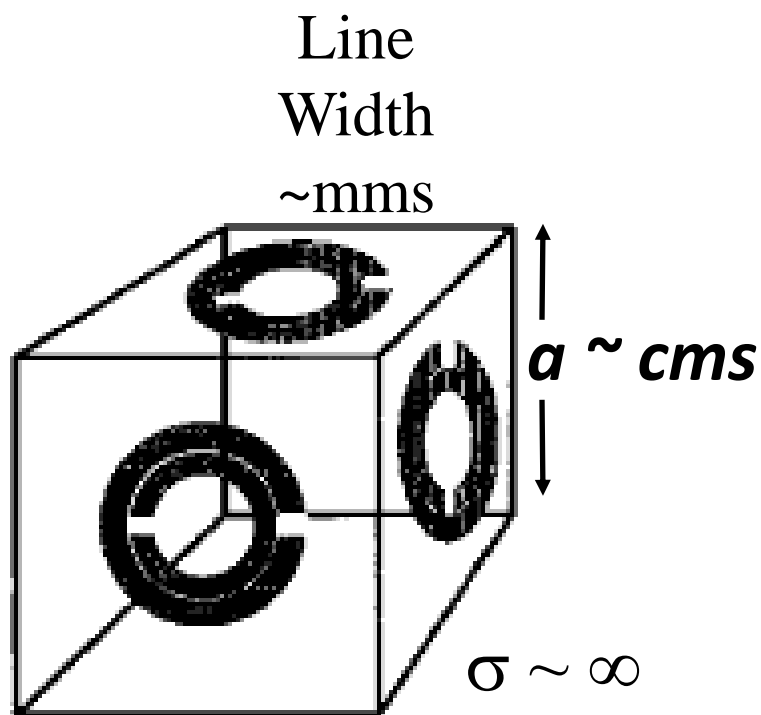


D. Bruce Burckel, Sandia National Laboratories

Sandia National Laboratories is a multi-program laboratory managed and operated by Sandia Corporation, a wholly owned subsidiary of Lockheed Martin Corporation, for the U.S. Department of Energy's National Nuclear Security Administration under contract DE-AC04-94AL85000.

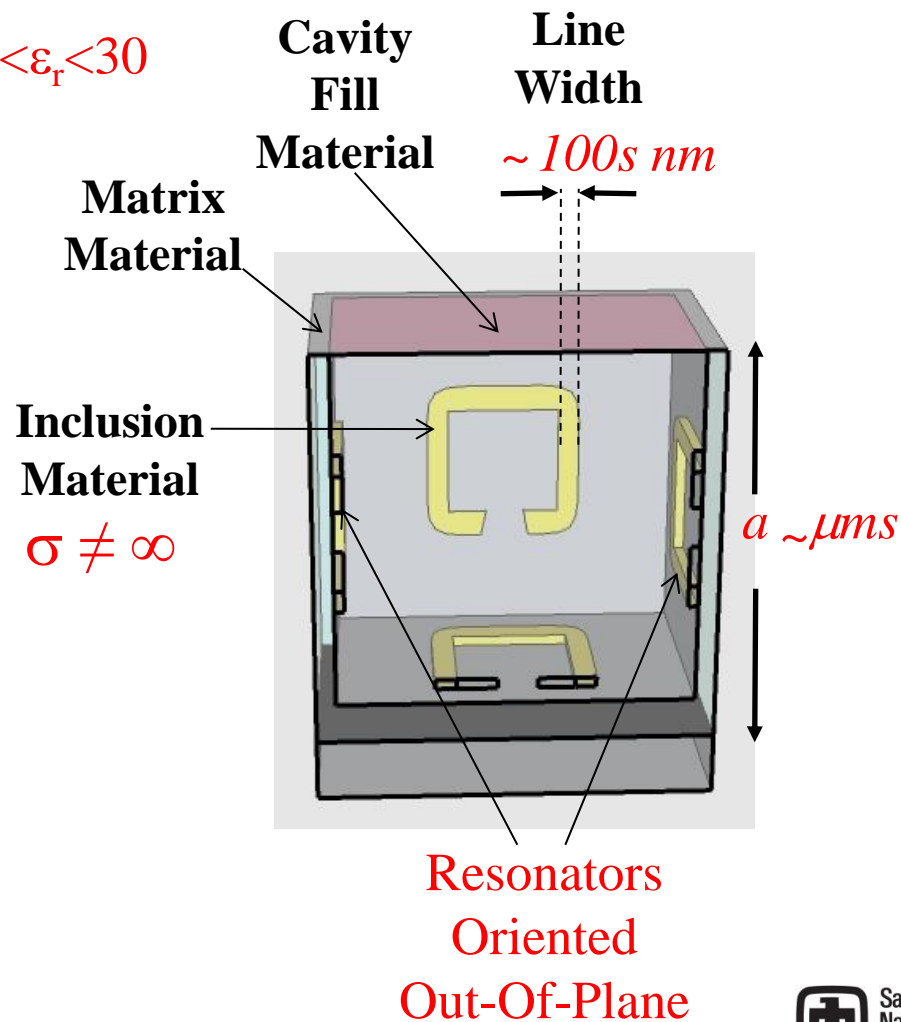
Translating a Pendry Cube from Microwave To Optical Frequencies

RF/Microwave



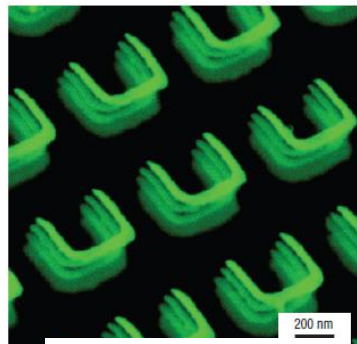
Infrared

$\mu_r \sim 1$
 $1 < \epsilon_r < 30$

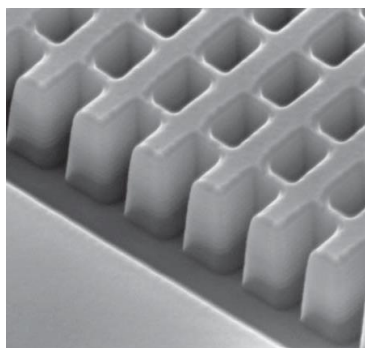


Examples of micro/nanoscale 3D Fabrication Approaches

Layer-by-layer

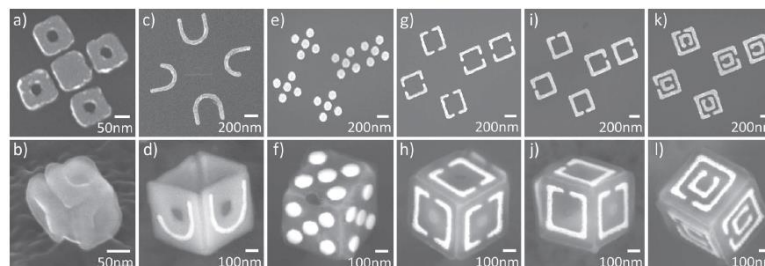
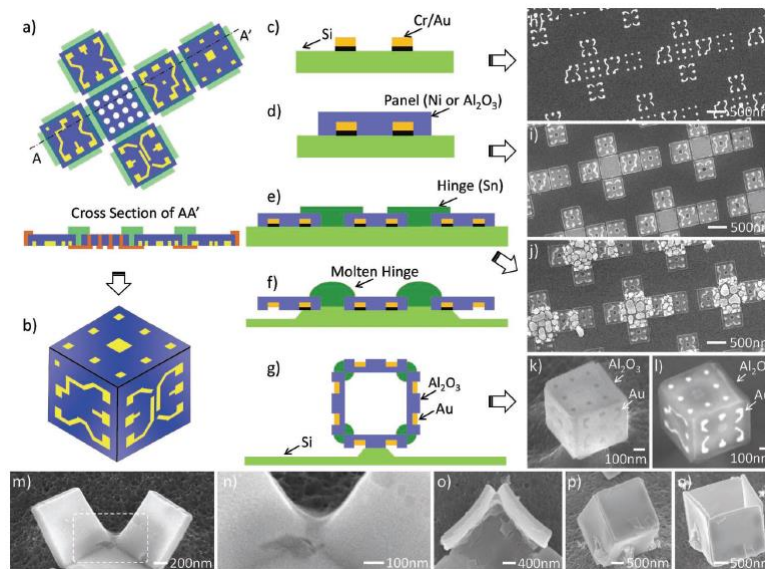


N. Liu, et. al.
Nat. Mat., 7,
pp 31-37, (2008)



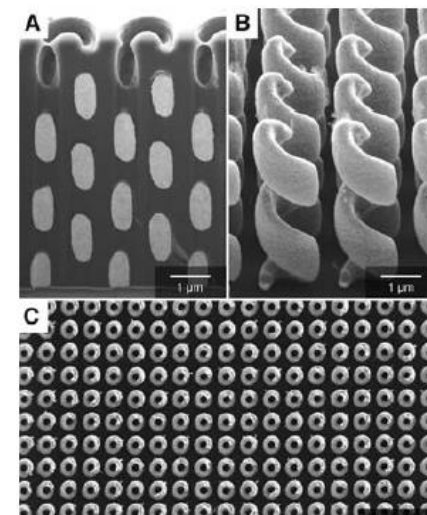
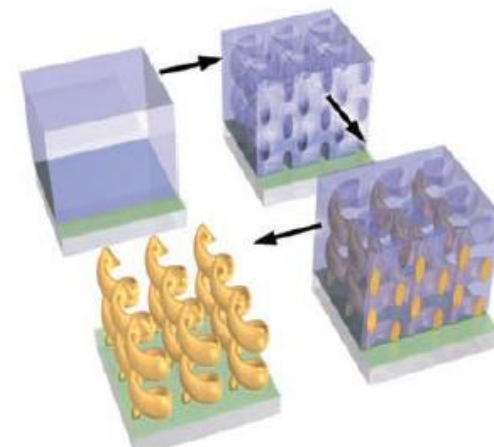
J. Valentine, et. al.
Nature, 455,
pp 376-U32, (2008)

Nano Origami



J.H. Cho, et. al. Small, 7,
pp 1943-1948, (2011)

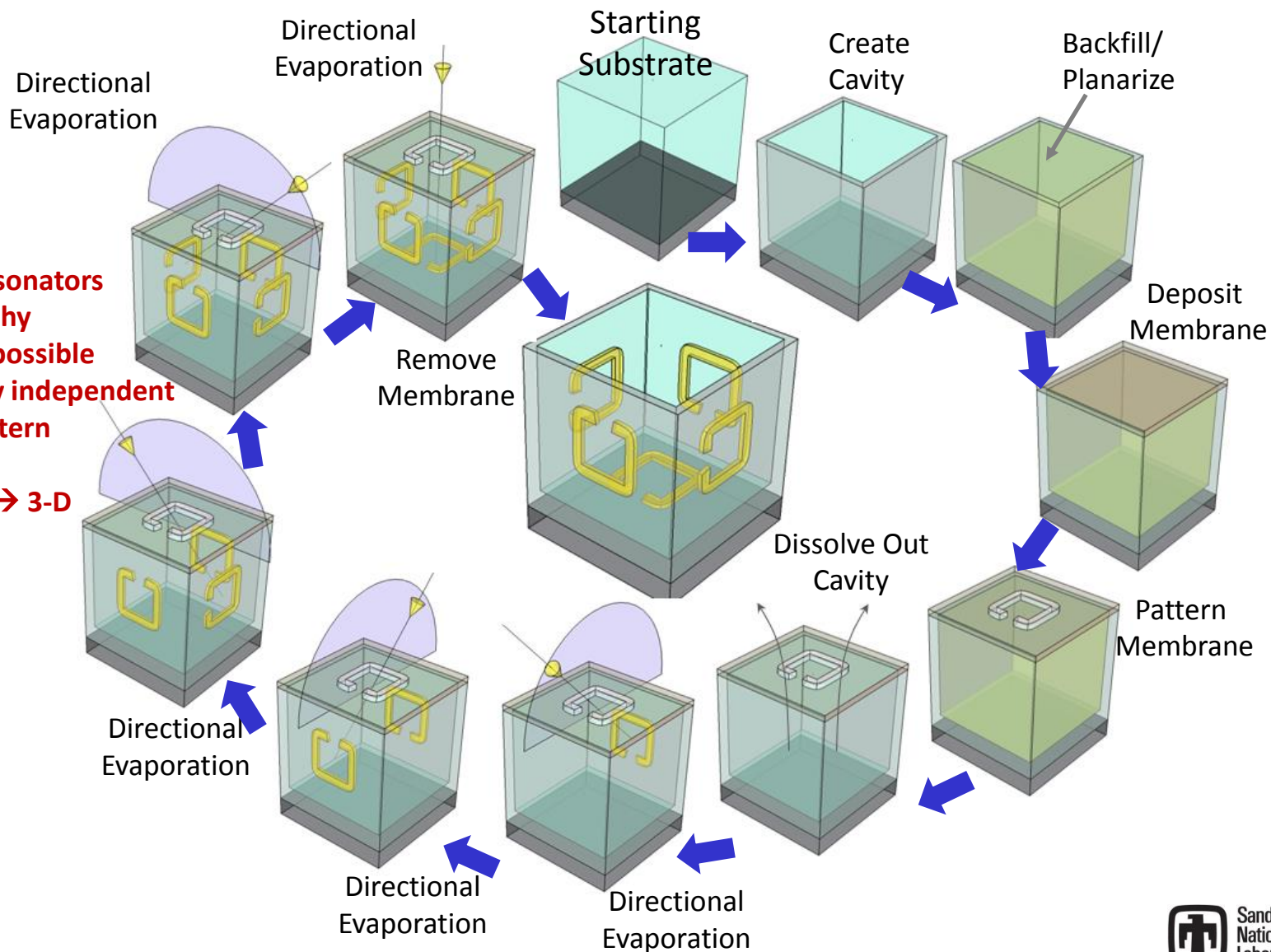
Direct Laser Write



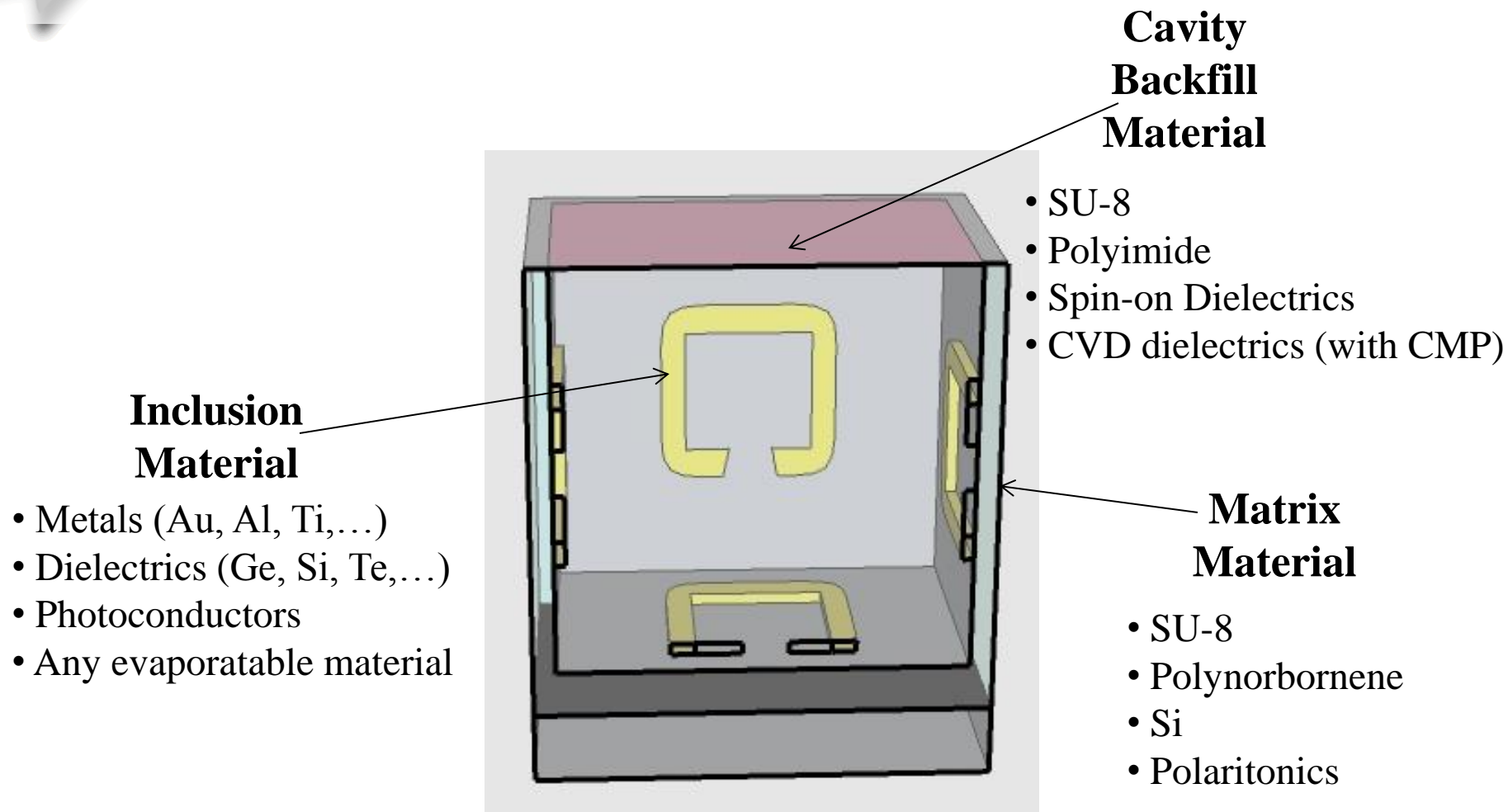
J.K. Gansel, et. al. Science, 325,
pp 1513-1515, (2009)

Membrane Projection Lithography: MPL

- Out-of-plane resonators
- Planar lithography
- Many patterns possible
- Cavity geometry independent of resonator pattern
- Scalable
- Layer-by-layer → 3-D

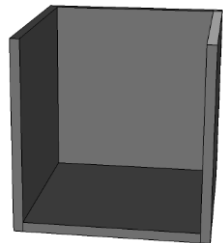


Material Components Available in MPL Fabrication

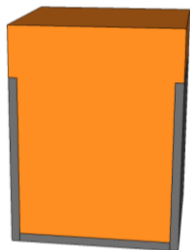


Material set for matrix, membrane and backfill must form a process-orthogonal set

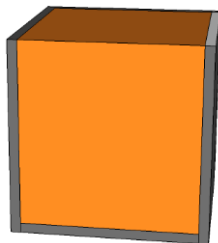
Organic MPL Process Flow



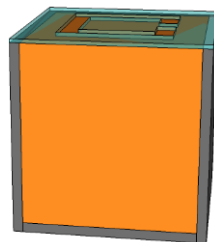
Create
Cavity



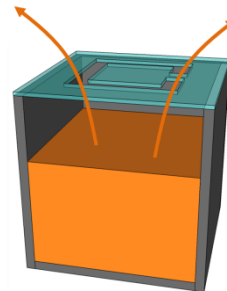
Sacrificial
Backfill



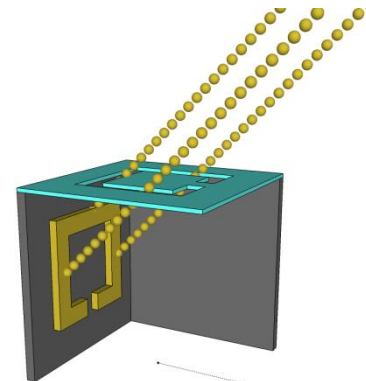
Planarize
Backfill



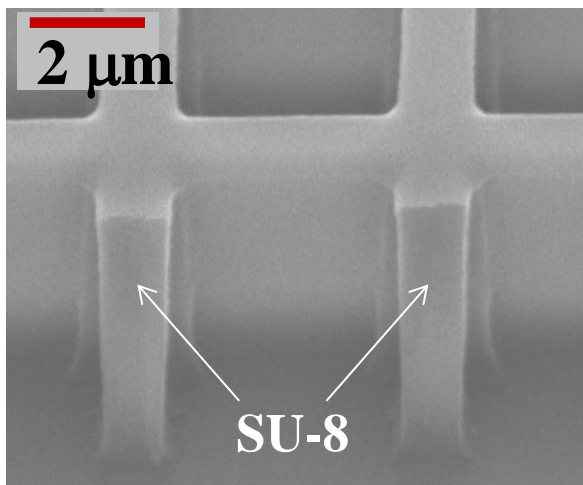
Deposit/Pattern
Membrane



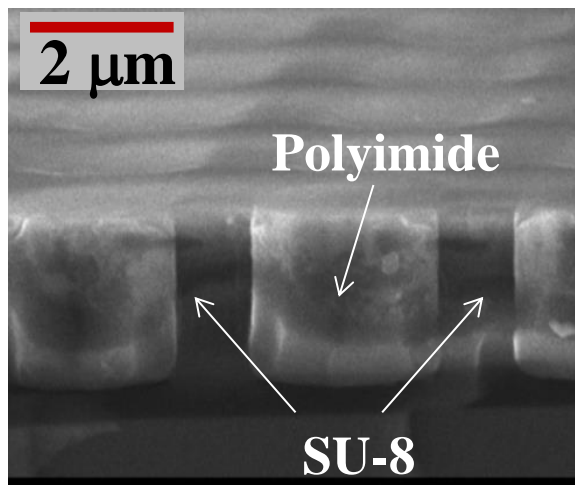
Dissolve Out
Backfill



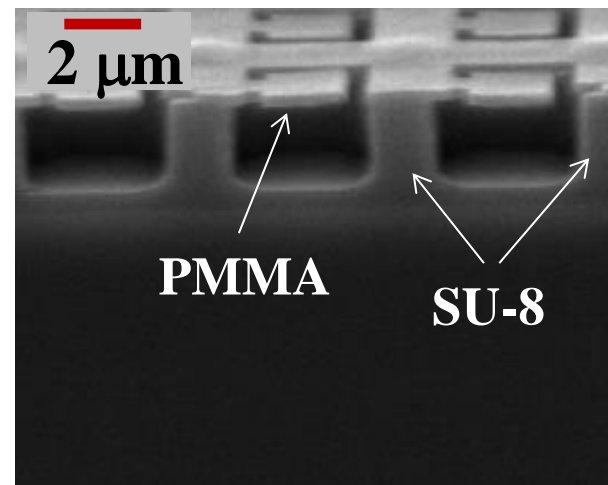
Directional
Processing



Create
Cavity

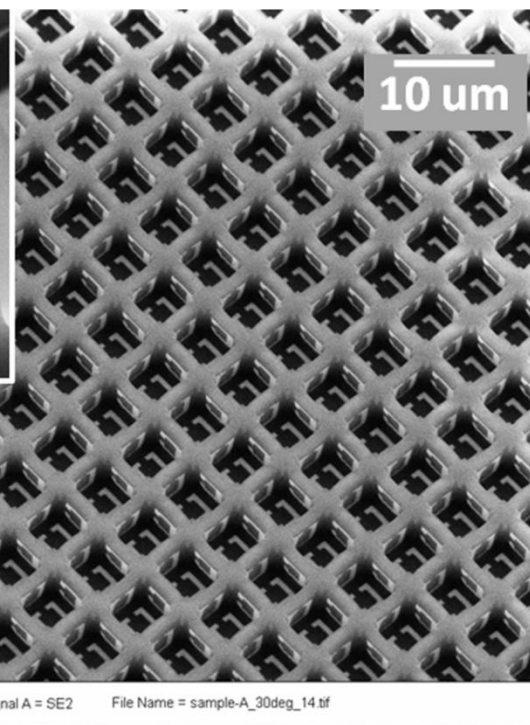
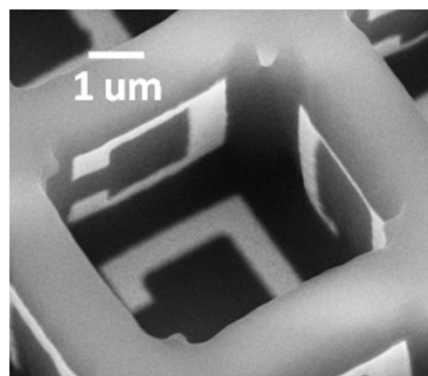
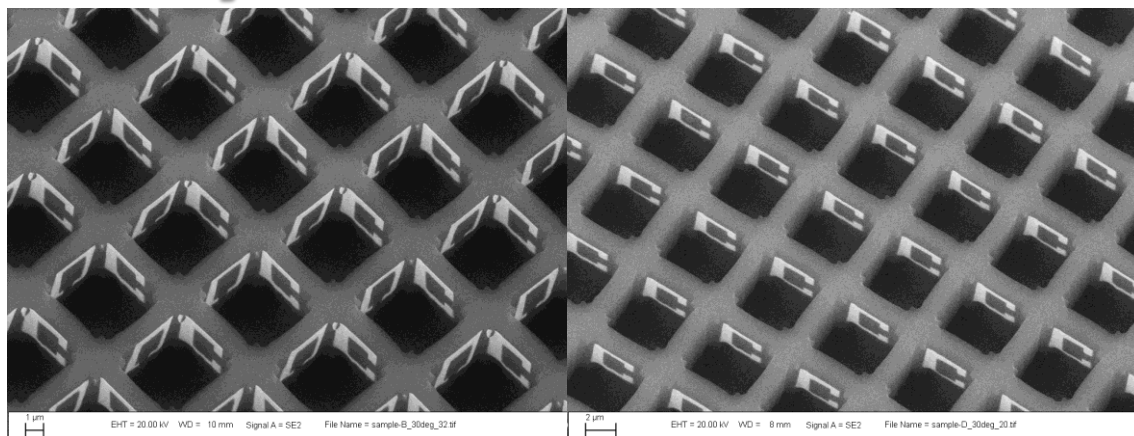
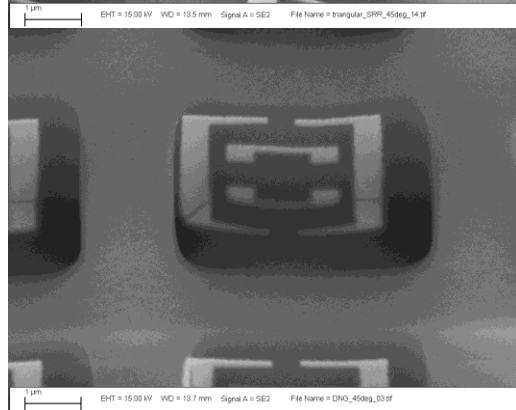
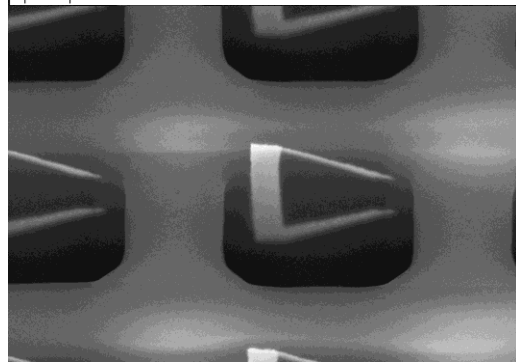
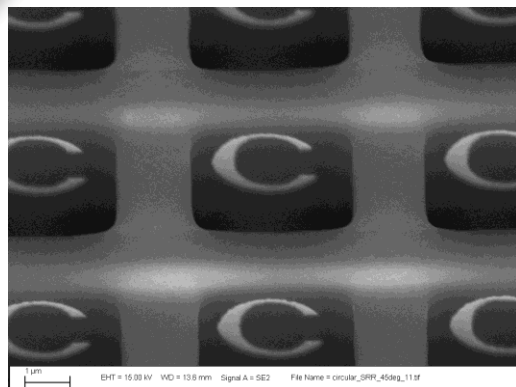


Planarize
Backfill

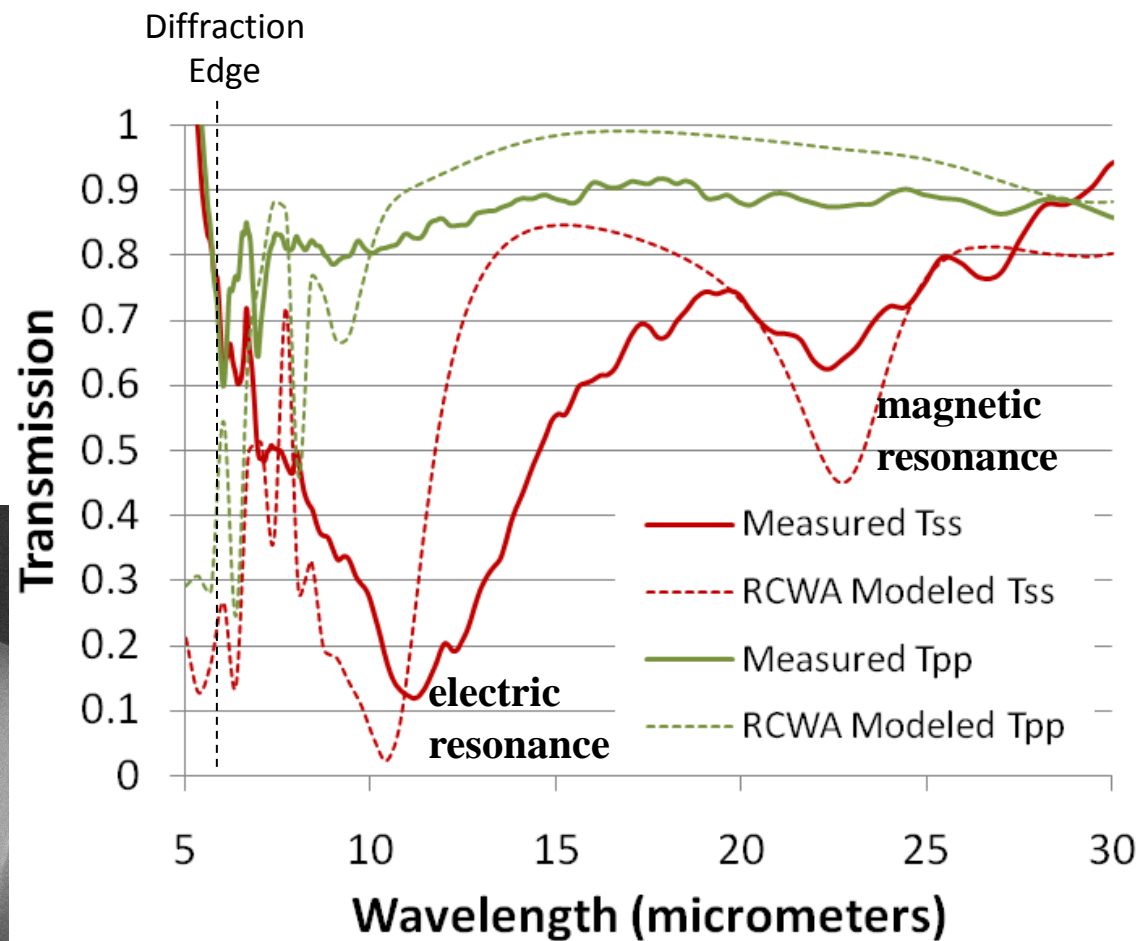
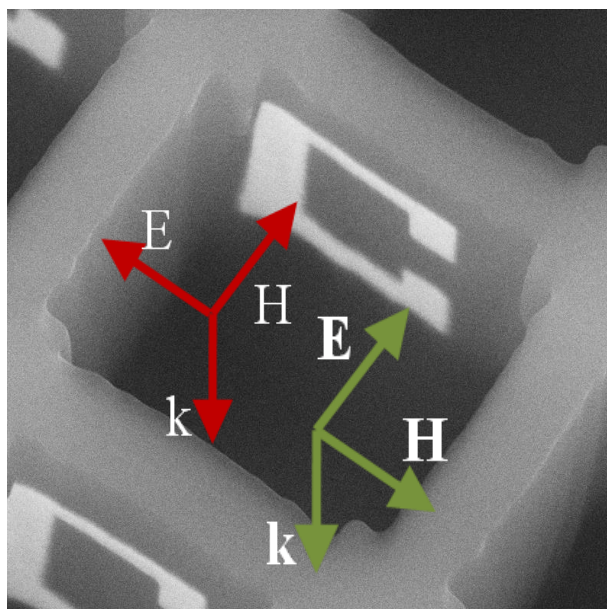
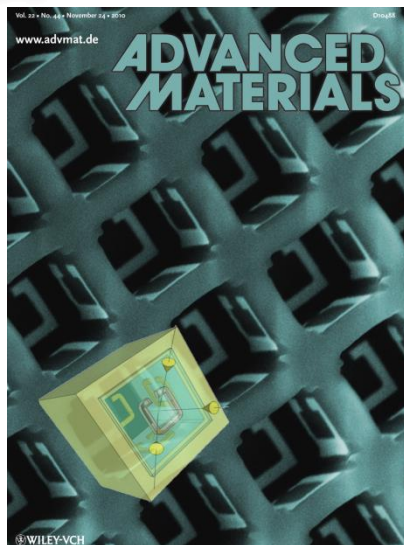


Dissolve Out
Backfill

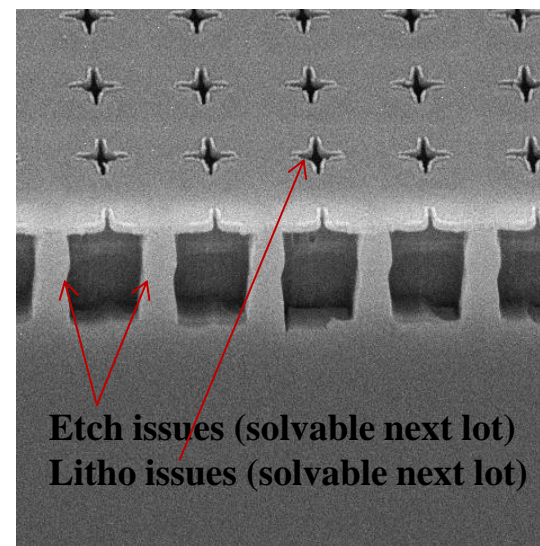
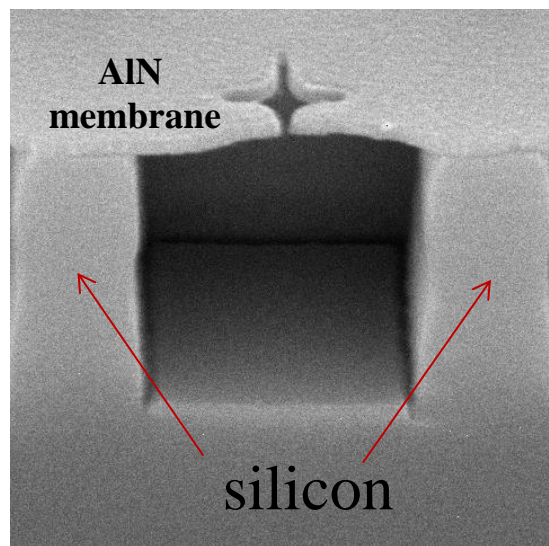
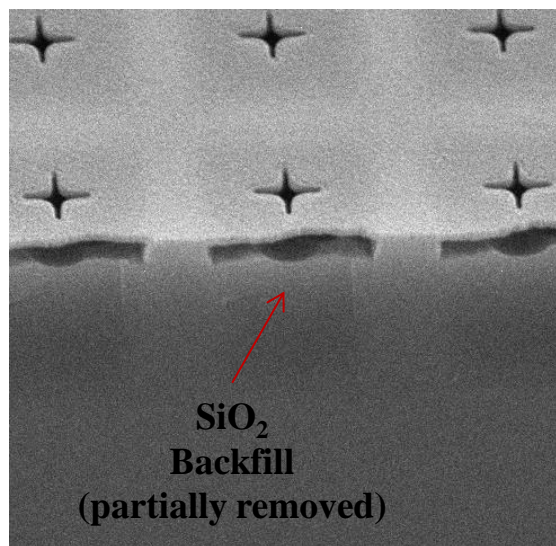
Micron-Scale Cubic Metamaterial Layers



Demonstration of Magnetic Polarization in the IR



MPL : Inorganic Material Set

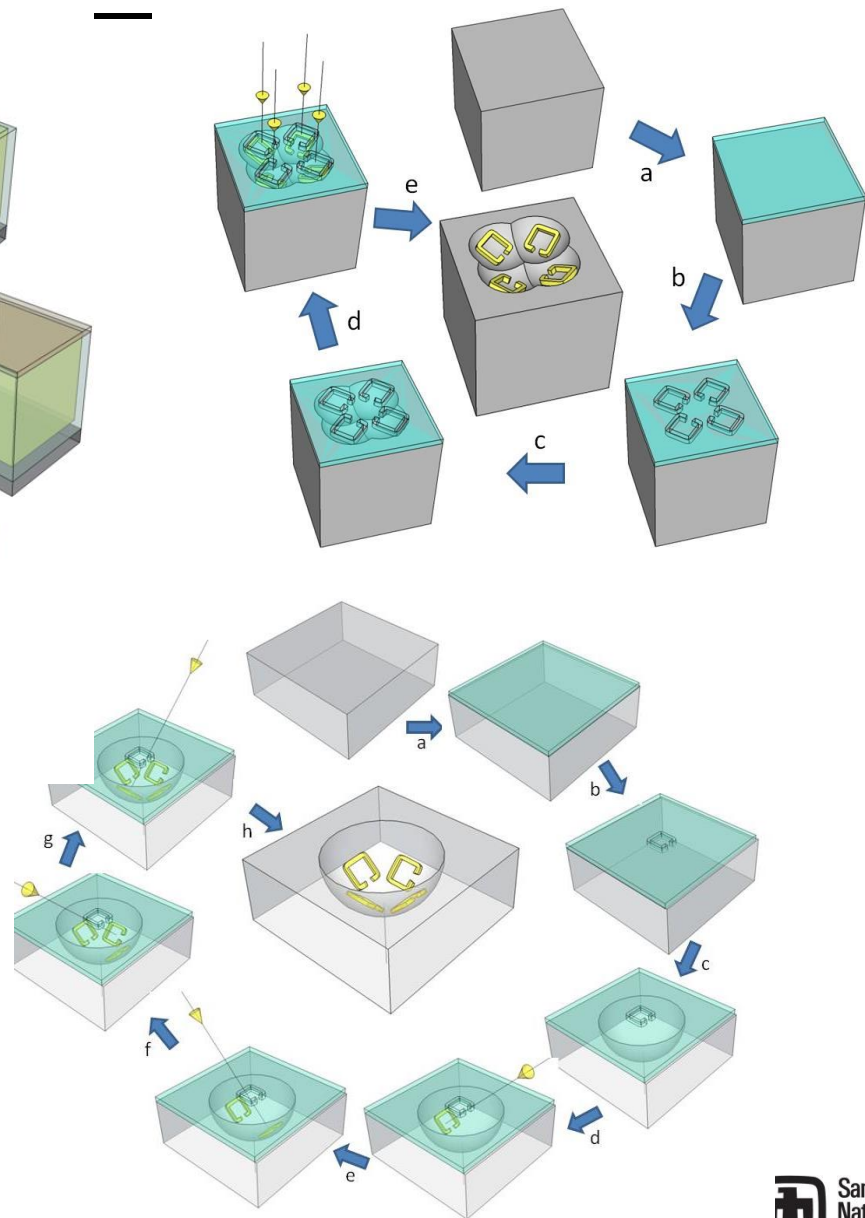
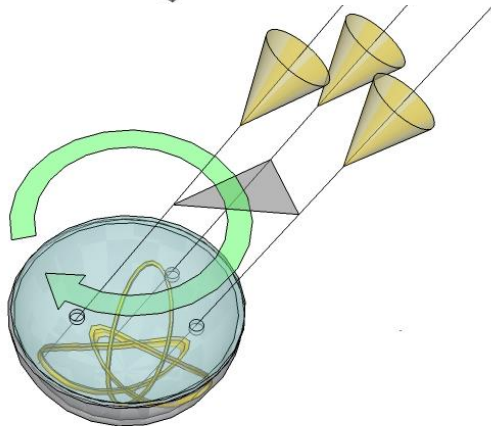
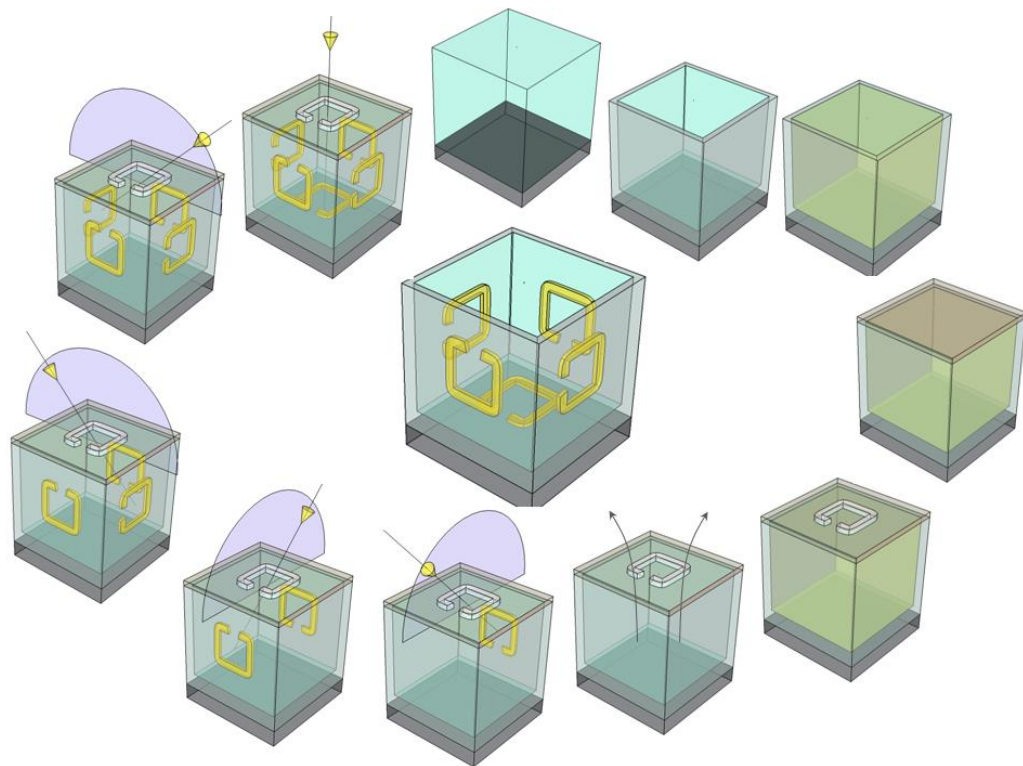


Lithography : Stepper

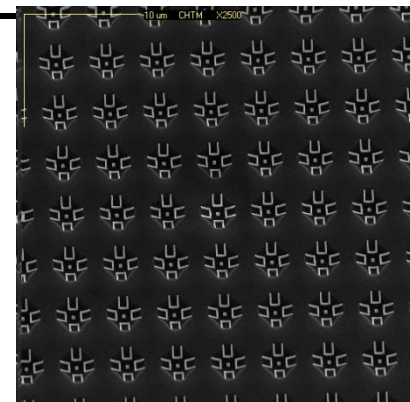
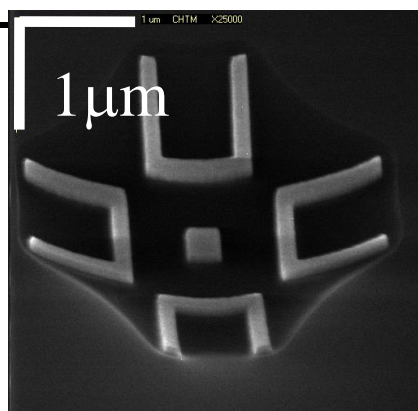
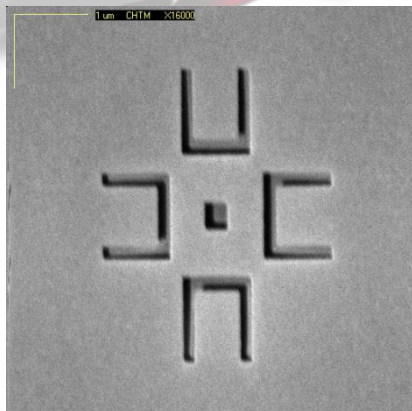
Inorganic backfill, CMP planarization

Subject of an upcoming LDRD : Fabrication of 3D Ics via MPL

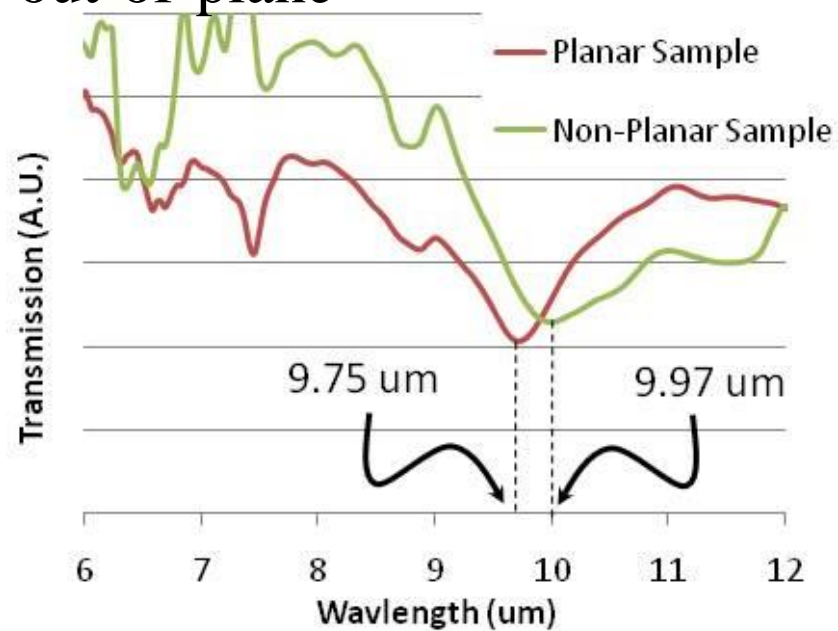
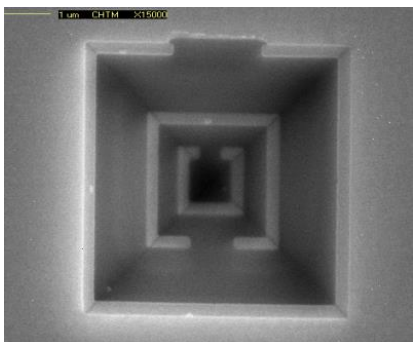
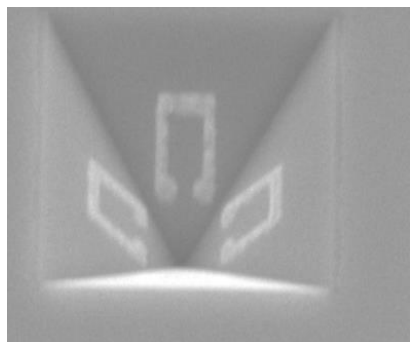
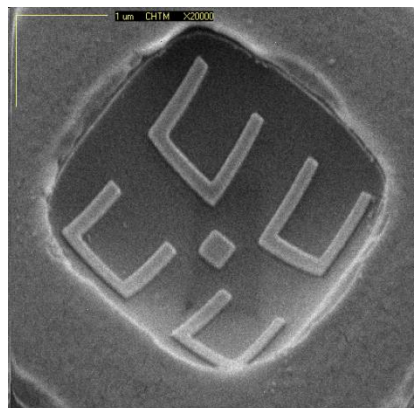
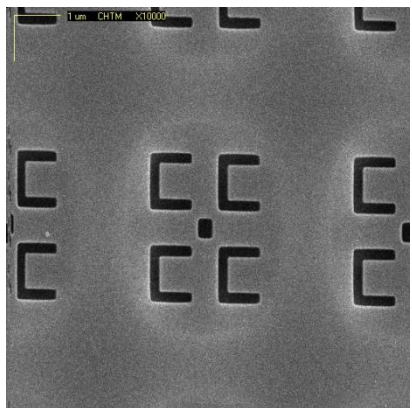
MPL At A Glance



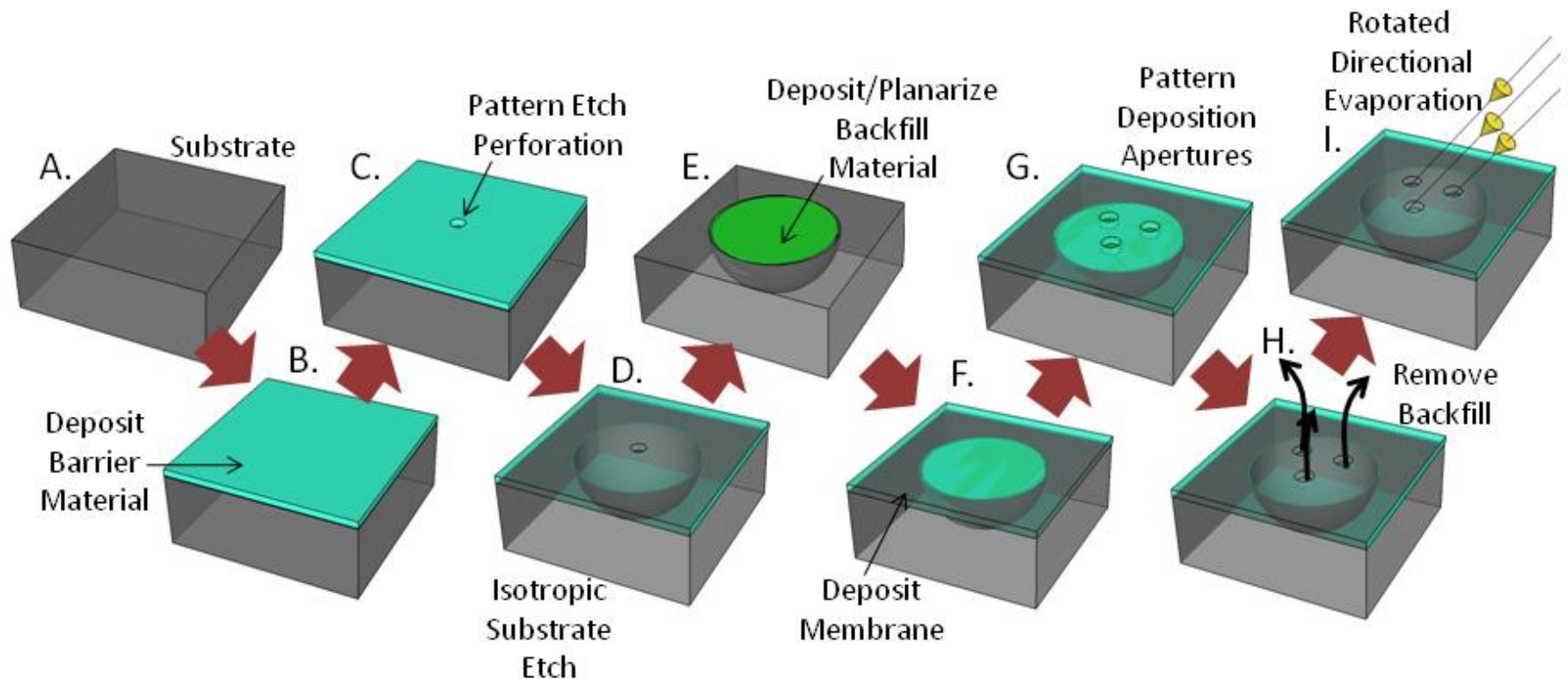
Examples of Single Evaporation SAMPL



Resonators 20^0
out-of-plane

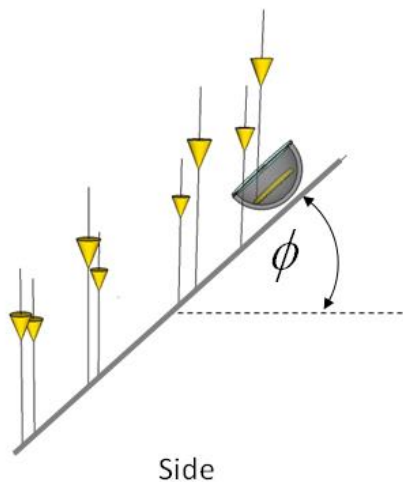
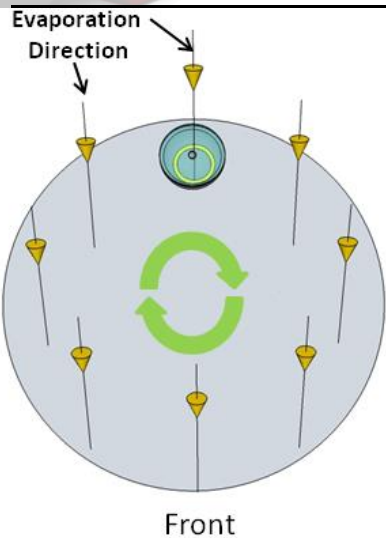


Two-Step Process Flow

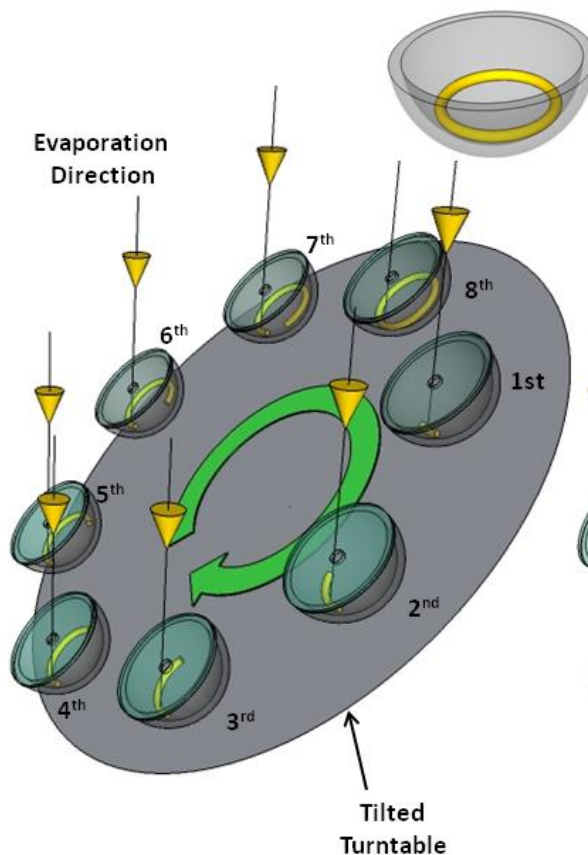


Cavity shape is now decoupled from perforation locations – wider variety of possible trace geometries.

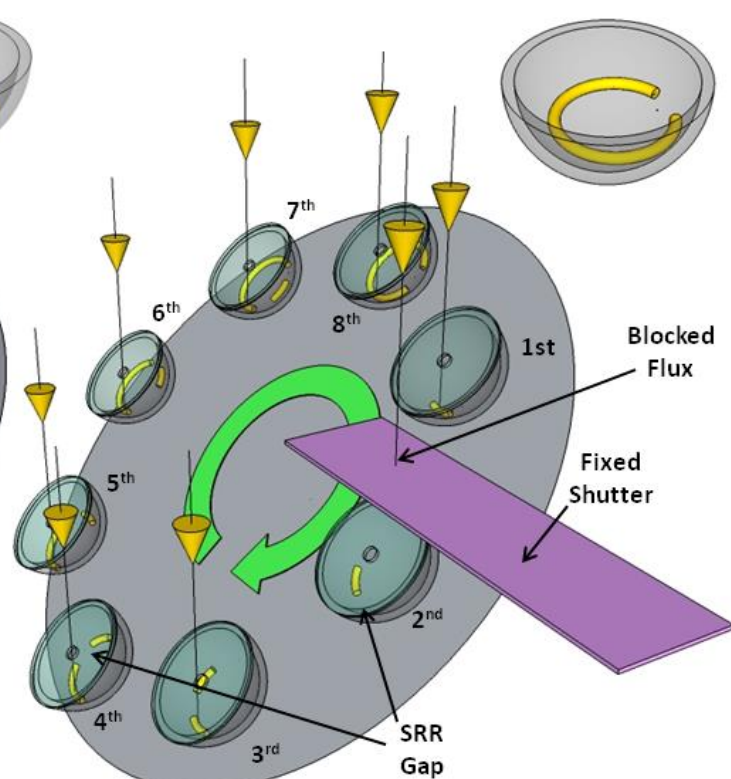
A More Practical Fabrication Approach



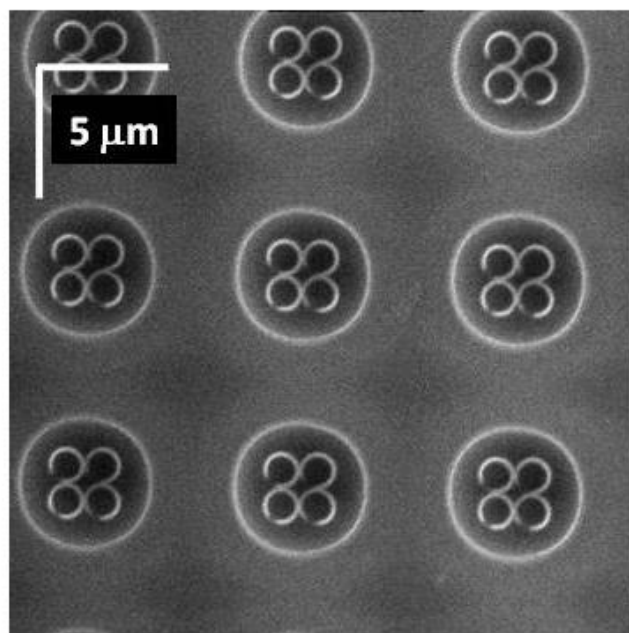
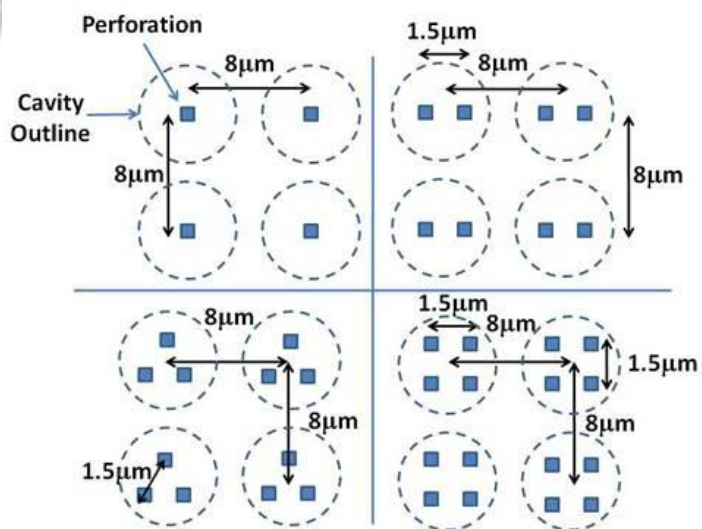
Closed Loops



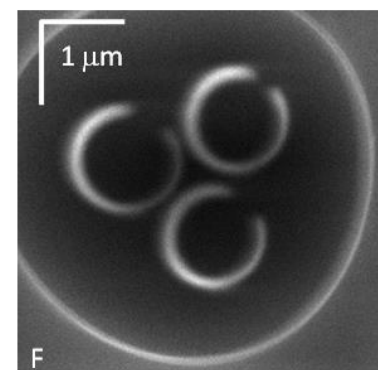
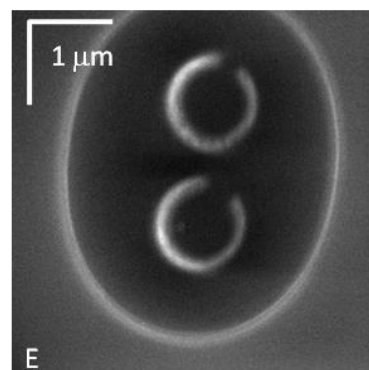
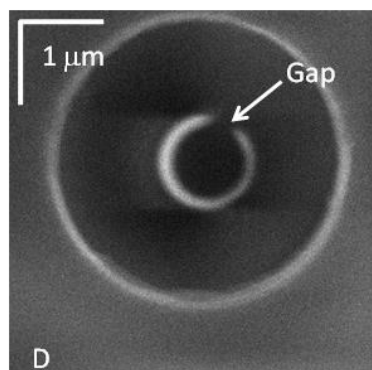
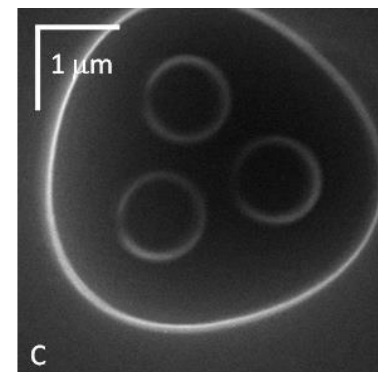
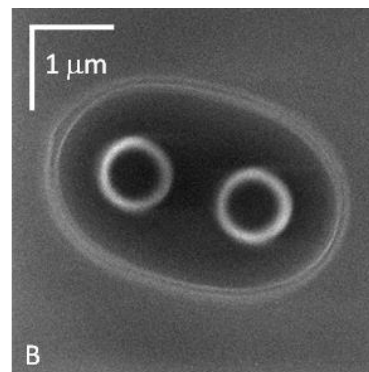
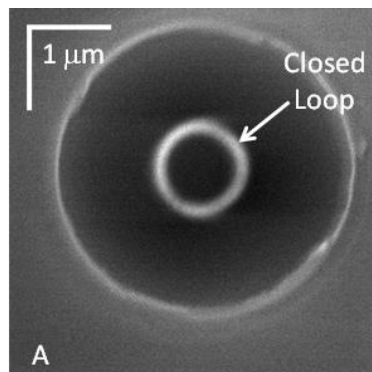
Split Loops



Preliminary Self- Aligned Fabrication Results



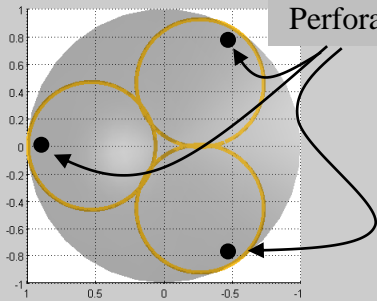
Self-aligned process flow – trace dependent
cavity shape



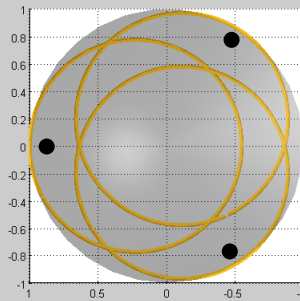
3D Multi-loop Traces

$$\phi = 40^\circ$$

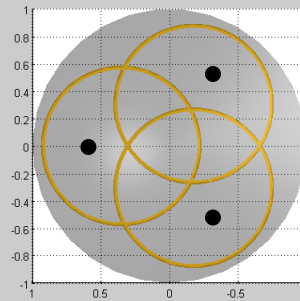
Membrane
Perforation



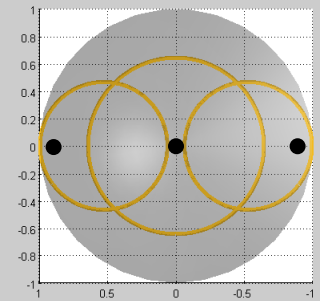
$$\phi = 60^\circ$$



$$\phi = 40^\circ$$



$$\phi = 40^\circ$$



A

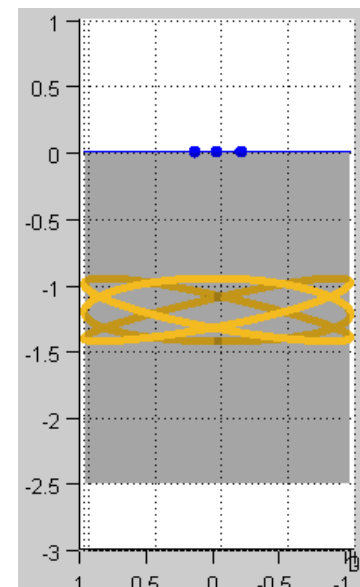
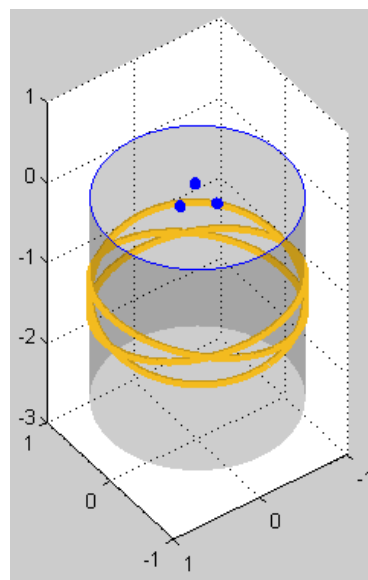
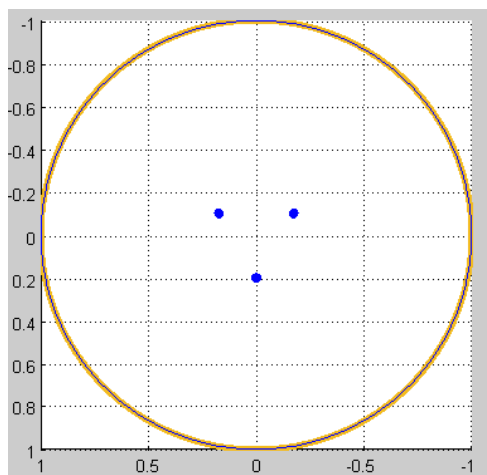
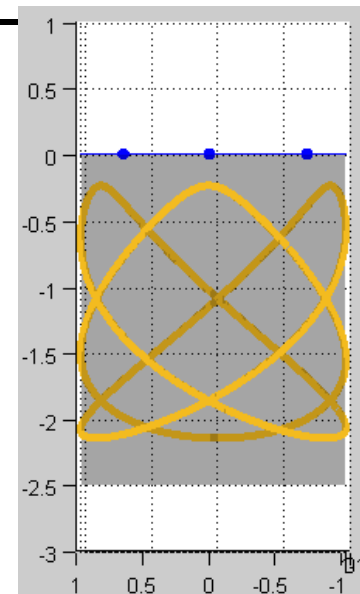
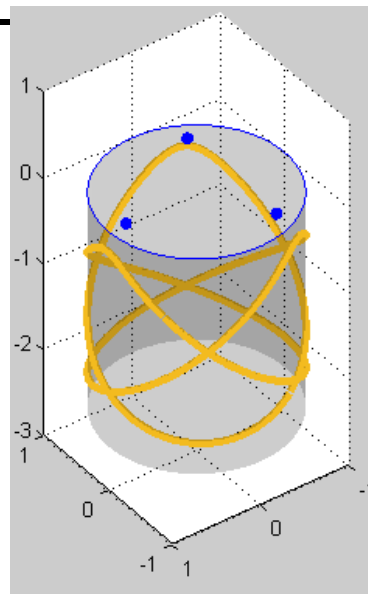
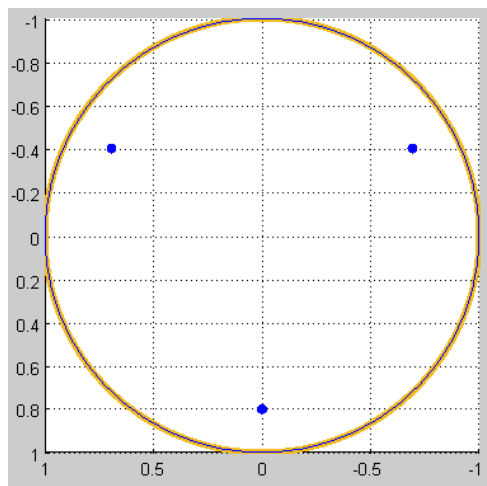
B

C

D

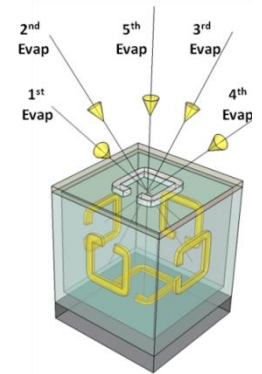
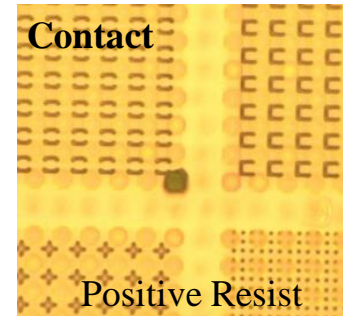
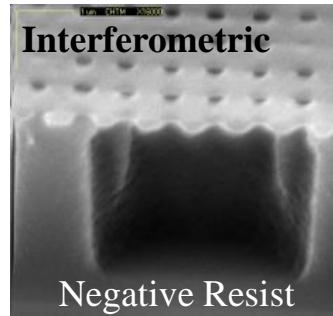
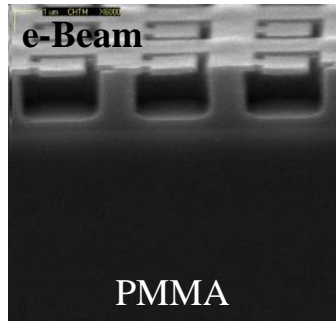
Simple geometrical variations lead to highly diverse 3D trace geometries

Dynamic MPL in a Cylindrical Cavity



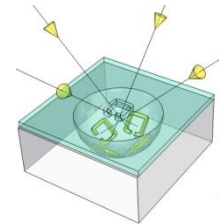
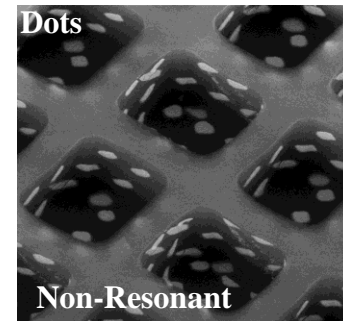
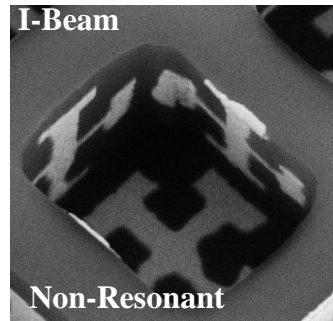
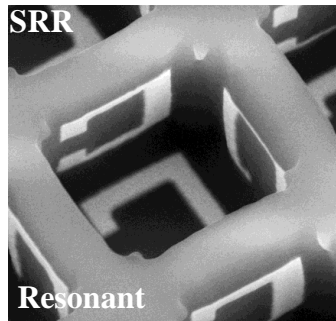
MPL Fabrication Parameter Space

Membrane Lithography



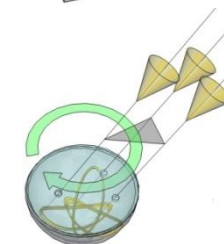
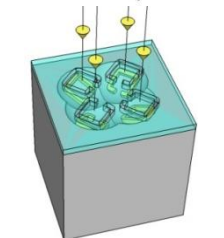
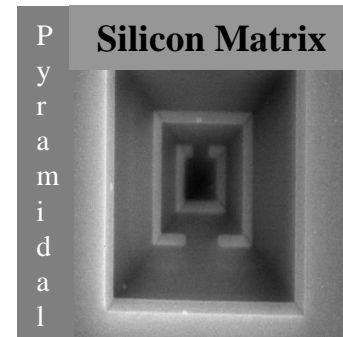
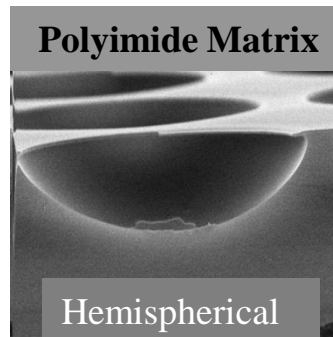
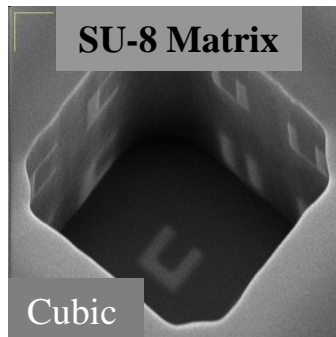
Membrane Material

Inclusion shape



Resonance

Matrix Material



Cavity Shape

Organic

Inorganic



Conclusions

- 1.) Membrane projection lithography is a manufacturable route to micron-scale 3D metamaterials.
- 2.) Identification of a process-orthogonal material set is critical to success of MPL.
- 3.) Fabrication in 3D opens a wide parameter space of potential unit cell design possibilities.
- 4.) CMOS compatible MPL should open a wide range of new applications.

Questions?